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BE CH DE FR GB LI(71) Applicant: HOECHST JAPAN LIMITED
10-16, 8-chome, Akasaka, Minato-ku
Tokyo (JP)

(72) Inventor: Przybilla, Klaus Jürgen
Baustasse 8
D-60322 Frankfurt (DE)
Inventor: Dammel, Ralph
8 Quimby Lane
Flemington, NJ 08822 (US)
Inventor: Pawlowski, Georg
Fritz-Kalle-Strasse 34
D-65187 Wiesbaden (DE)
Inventor: Kudo, Takanori Hoechst Japan
Limited
Advanced Technology Lab.,
3-2, Minamidai 1-chome
Kawagoe, Saitama (JP)
Inventor: Masuda, Seiya, Hoechst Japan
Limited
Advanced Technology Lab.,
3-2, Minamidai 1-chome
Kawagoe, Saitama (JP)

Inventor: Kinoshita, Yoshiaki, Hoechst Japan
Limited
Advanced Technology Lab.,
3-2, Minamidai 1-chome
Kawagoe, Saitama (JP)

Inventor: Suehiro, Natsumi, Hoechst Japan
Limited
Advanced Technology Lab.,
3-2, Minamidai 1-chome
Kawagoe, Saitama (JP)

Inventor: Padmanaban, Munirathna, Hoechst
Japan Limited
Advanced Technology Lab.,
3-2, Minamidai 1-chome
Kawagoe, Saitama (JP)

Inventor: Okazaki, Hiroshi, Hoechst Japan
Limited
Advanced Technology Lab.,
3-2, Minamidai 1-chome
Kawagoe, Saitama (JP)

Inventor: Endo, Hajime, Hoechst Japan
Limited
Advanced Technology Lab.,
3-2 Minamidai 1-chome
Kawagoe, Saitama (JP)

(74) Representative: WILHELMS, KILIAN &
PARTNER Patentanwälte
Eduard-Schmid-Strasse 2
D-81541 München (DE)

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(54) Positive-working radiation-sensitive mixture.

(57) A novel positive-working radiation-sensitive mixture having a high sensitivity to radiation in a short-wavelength UV region is provided which can be developed in an aqueous alkaline solution, has a stable acid latent image and is used for the production of a semiconductor. The mixture comprises, as indispensable components, a) a binder insoluble in water but soluble in an aqueous alkaline solution, b) a compound having at least one bond cleavable with an acid, c) a compound capable of producing an acid upon radiation, and d) a basic ammonium compound or d₂) a basic sulfonium compound.